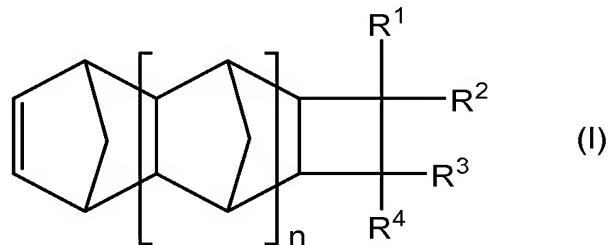


**Amendments to Claims**

1. (Previously Presented) A copolymer comprising a repeat unit derived from
  - (a) at least one repeat unit derived from an ethylenically unsaturated compound having at least one fluorine atom covalently attached to an ethylenically unsaturated carbon atom; and
  - (b) at least one repeat unit derived from an ethylenically unsaturated compound having the structure:



wherein n is 0, 1, or 2;

R<sup>1</sup>, R<sup>2</sup>, R<sup>3</sup> and R<sup>4</sup> are independently H, OR<sup>5</sup>, halogen, alkyl or alkoxy of 1 to 10 carbon atoms, optionally substituted by halogen or ether oxygens, Y, C(R<sub>f</sub>)(R<sub>f'</sub>)OR<sup>5</sup>, R<sup>6</sup>Y or OR<sup>6</sup>Y;

Y is COZ or SO<sub>2</sub>Z;

R<sup>5</sup> is hydrogen or an acid-labile protecting group;

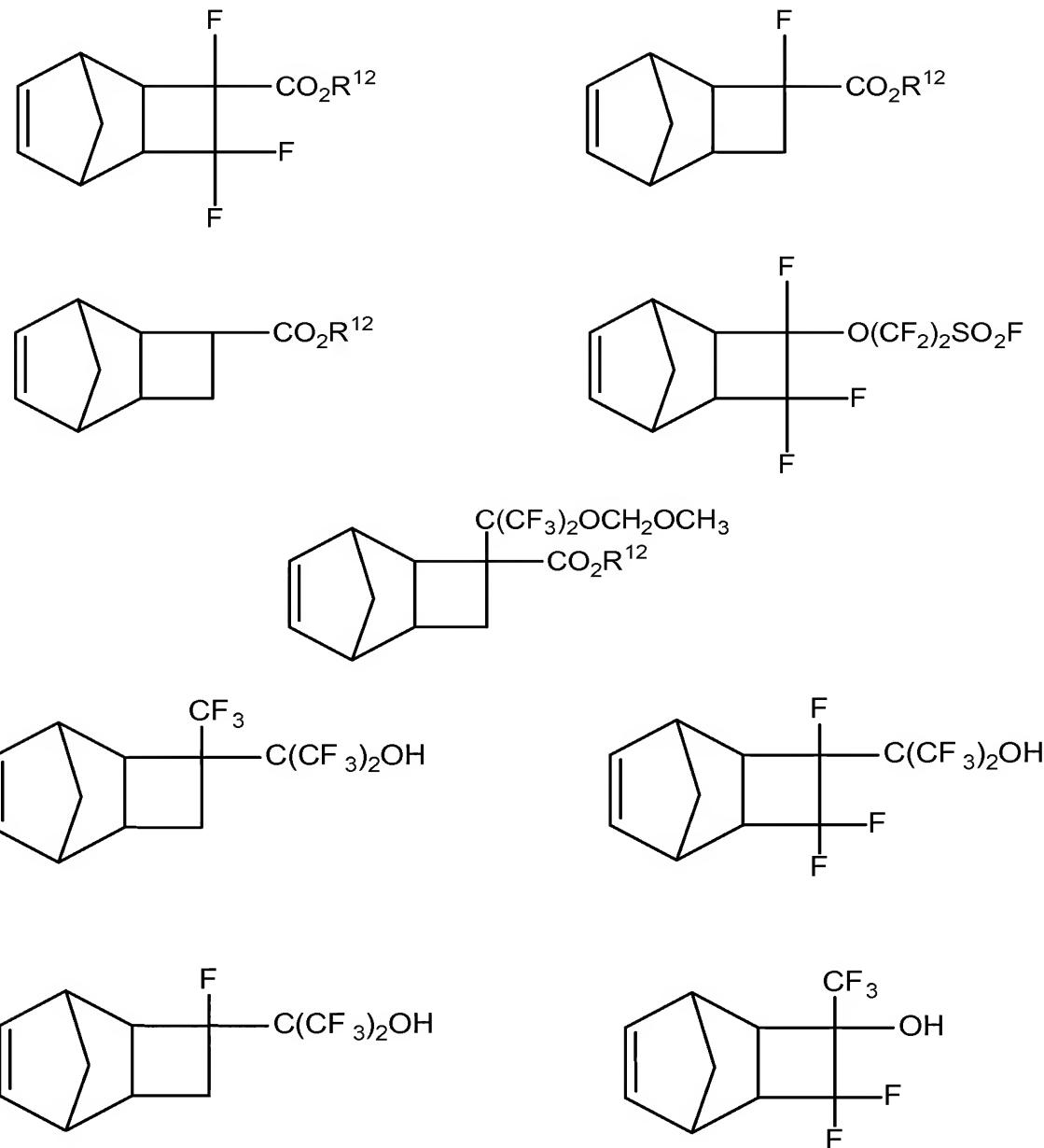
R<sub>f</sub> and R<sub>f'</sub> are the same or different fluoroalkyl groups of 1 to 10 carbon atoms or taken together are (CF<sub>2</sub>)<sub>m</sub> where m is 2 to 10;

R<sup>6</sup> is an alkylene group of 1 to 20 carbon atoms, optionally substituted by halogen or ether oxygen;

Z is OH, halogen, or OR<sup>7</sup>; and

R<sup>7</sup> is an alkyl group of 1 to 20 carbon atoms, with the proviso that at least one of R<sup>1</sup>, R<sup>2</sup>, R<sup>3</sup> and R<sup>4</sup> is Y, OR<sup>5</sup>, C(R<sub>f</sub>)(R<sub>f'</sub>)OR<sup>5</sup>, R<sup>6</sup>Y or OR<sup>6</sup>Y, and the proviso that if R<sup>1</sup> (or R<sup>3</sup>) is OH, R<sup>2</sup> (or R<sup>4</sup>) is not OH or halogen.

2. (Previously Presented) The copolymer of Claim 1, wherein the compound having structure (I) is selected from the group consisting of:



wherein  $\text{R}^{12}$  is an alkyl group of 1 to 20 carbon atoms.

3. (Previously Presented) The copolymer of Claim 1, wherein the at least one ethylenically unsaturated compound having at least one fluorine atom covalently attached to an ethylenically unsaturated carbon atom is a fluorooolefin which comprises 2 to 20 carbon atoms.

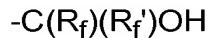
4. (Previously Presented) The copolymer of Claim 3, wherein the fluorooolefin is selected from the group consisting of tetrafluoroethylene; hexafluoropropylene;

chlorotrifluoroethylene; vinylidene fluoride; vinyl fluoride; perfluoro-(2,2-dimethyl-1,3-dioxole); perfluoro-(2-methylene-4-methyl-1,3-dioxolane);  $\text{CF}_2=\text{CFO}(\text{CF}_2)_t\text{CF}=\text{CF}_2$ , wherein t is 1 or 2; and  $\text{R}_f''\text{OCF}=\text{CF}_2$  wherein  $\text{R}_f''$  is a saturated fluoroalkyl group of from 1 to 10 carbon atoms.

5. (Previously Presented) The copolymer of Claim 4, wherein the fluoroolefin is tetrafluoroethylene.

6. (Previously Presented) The copolymer of Claim 1, further comprising a unit containing a fluoroalcohol group or a protected fluoroalcohol group.

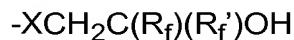
7. (Previously Presented) The copolymer of Claim 6, wherein the fluoroalcohol group or the protected fluoroalcohol group is derived from at least one ethylenically unsaturated compound containing a fluoroalcohol group having the structure:



wherein  $\text{R}_f$  and  $\text{R}_f'$  are the same or different fluoroalkyl groups of from 1 to 10 carbon atoms or taken together are  $(\text{CF}_2)_m$  wherein m is 2 to 10.

8. (Previously Presented) The copolymer of Claim 7, wherein  $\text{R}_f$  and  $\text{R}_f'$  are perfluoroalkyl groups.

9. (Previously Presented) The copolymer of Claim 1, further comprising a unit containing a fluoroalcohol group having the structure:

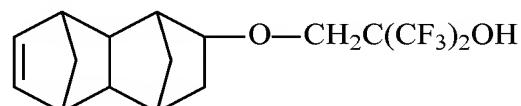
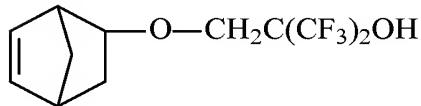
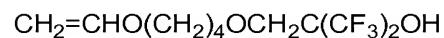
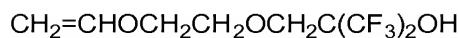
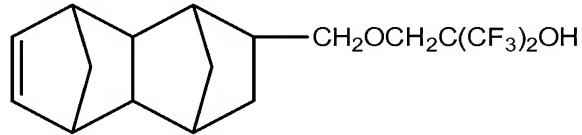
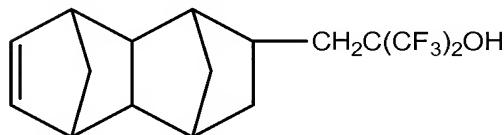
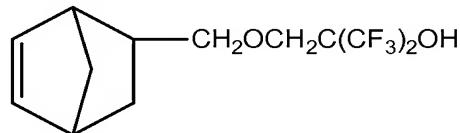
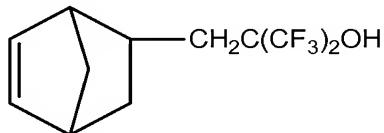


wherein  $\text{R}_f$  and  $\text{R}_f'$  are the same or different fluoroalkyl groups of from 1 to 10 carbon atoms or taken together are  $(\text{CF}_2)_m$  wherein m is 2 to 10; and X is an element from Group VA or Group VIA of the Periodic Table of the Elements.

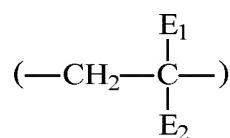
10. (Previously Presented) The copolymer of Claim 9, wherein X is selected from the group consisting of oxygen, sulfur, nitrogen and phosphorous.

11. (Previously Presented) The copolymer of Claim 10, wherein X is oxygen.

12. (Previously Presented) The copolymer of Claim 7, wherein fluoroalcohol group or the protected fluoroalcohol group is derived from a monomer selected from the group consisting of:



13. (Previously Presented) The copolymer of Claim 1 further comprising at least one acid-containing or protected acid-containing group of structural unit:



wherein E<sub>1</sub> is H or C<sub>1</sub>-C<sub>12</sub> alkyl; E<sub>2</sub> is CO<sub>2</sub>E<sub>3</sub>, SO<sub>3</sub>E, or other acidic group; and E and E<sub>3</sub> are independently selected from the group of H, unsubstituted C<sub>1</sub>-C<sub>12</sub> alkyl, and heteroatom substituted C<sub>1</sub>-C<sub>12</sub> alkyl.

14. (Previously Presented) The copolymer of Claim 13, wherein the heteroatom is selected from the group consisting of oxygen, nitrogen, sulfur, halogen and phosphorus atoms.

15. (Previously Presented) The copolymer of Claim 14, wherein the heteroatom is oxygen, and the heteroatom substituted C<sub>1</sub>-C<sub>12</sub> alkyl further comprises a hydroxyl group.

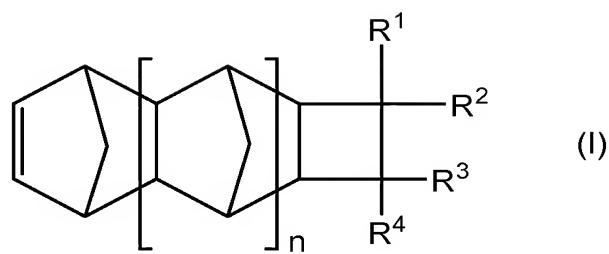
16. (Previously Presented) The copolymer of Claim 13, wherein the acid-containing or protected acid-containing group is derived from a carboxylic acid-containing monomer.

17. (Previously Presented) The copolymer of Claim 13, wherein the acid-containing or protected acid-containing group is derived from a monomer selected from the group consisting of tert-butyl acrylate; 2-methyl-2-adamantyl acrylate; 2-methyl-2-norbornyl acrylate and acrylic acid.

18. (Previously Presented) The copolymer of Claim 1, further comprising at least one group derived from a polar monomer.

19. (Previously Presented) A photoresist composition comprising:

- (1) a fluorine-containing copolymer, wherein the fluorine-containing copolymer comprises:
  - (a) at least one repeat unit derived from an ethylenically unsaturated compound having at least one fluorine atom covalently attached to an ethylenically unsaturated carbon atom; and
  - (b) at least one repeat unit derived from an ethylenically unsaturated compound having the structure:



wherein n is 0, 1, or 2;

R<sup>1</sup>, R<sup>2</sup>, R<sup>3</sup> and R<sup>4</sup> are independently H, OR<sup>5</sup>, halogen, alkyl or alkoxy of 1 to 10 carbon atoms, optionally substituted by halogen or ether oxygens, Y, C(R<sub>f</sub>)(R<sub>f'</sub>)OR<sup>5</sup>, R<sup>6</sup>Y or OR<sup>6</sup>Y;

Y is COZ or SO<sub>2</sub>Z;

R<sup>5</sup> is hydrogen or an acid-labile protecting group;

R<sub>f</sub> and R<sub>f'</sub> are the same or different fluoroalkyl groups of 1 to 10 carbon atoms or taken together are (CF<sub>2</sub>)<sub>m</sub> where m is 2 to 10;

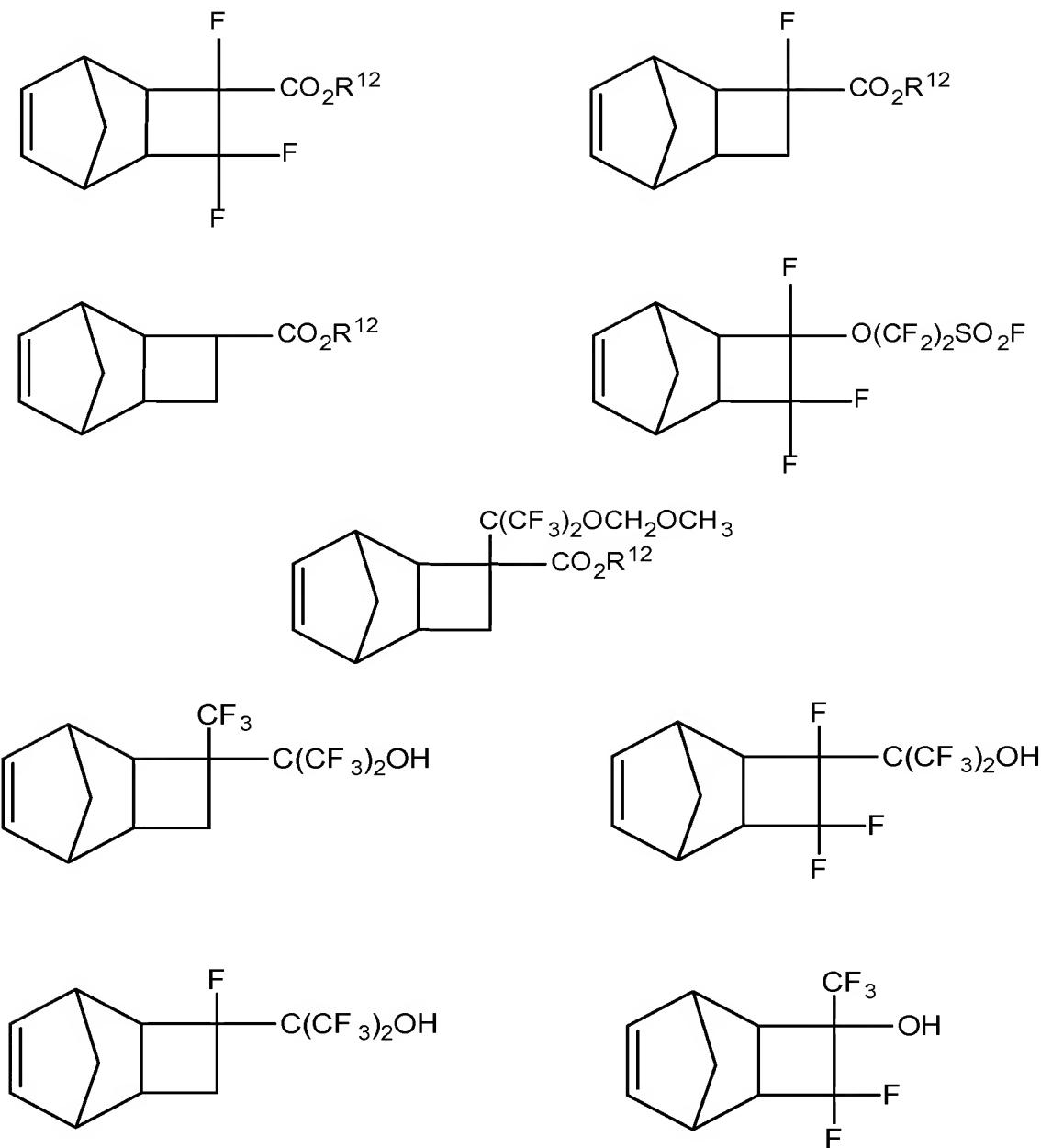
R<sup>6</sup> is an alkylene group of 1 to 20 carbon atoms, optionally substituted by halogen or ether oxygen;

Z is OH, halogen, or OR<sup>7</sup>; and

R<sup>7</sup> is an alkyl group of 1 to 20 carbon atoms, with the proviso that at least one of R<sup>1</sup>, R<sup>2</sup>, R<sup>3</sup> and R<sup>4</sup> is OR<sup>5</sup>, Y, C(R<sub>f</sub>)(R<sub>f'</sub>)OR<sup>5</sup>, R<sup>6</sup>Y or OR<sup>6</sup>Y, and the proviso that if R<sup>1</sup> (or R<sup>3</sup>) is OH, R<sup>2</sup> (or R<sup>4</sup>) is not OH or halogen; and

(2) a photoactive component.

20. (Previously Presented) The photoresist composition of Claim 19, wherein the monomer having structure (I) in the fluorine-containing copolymer is selected from the group consisting of:



wherein  $\text{R}^{12}$  is an alkyl group of 1 to 20 carbon atoms.

21. (Original) The photoresist composition of Claim 19, wherein (a) is a fluorooolefin comprising 2 to 20 carbon atoms.

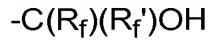
22. (Original) The photoresist composition of Claim 21, wherein the fluorooolefin is selected from the group consisting of tetrafluoroethylene; hexafluoropropylene; chlorotrifluoroethylene; vinylidene fluoride; vinyl fluoride; perfluoro-(2,2-dimethyl-1,3-dioxole); perfluoro-(2-methylene-4-methyl-1,3-dioxolane);  $\text{CF}_2=\text{CFO}(\text{CF}_2)_t\text{CF}=\text{CF}_2$ ,

wherein t is 1 or 2; and  $R_f''OCF=CF_2$ , wherein  $R_f''$  is a saturated fluoroalkyl group of from 1 to 10 carbon atoms.

23. (Original) The photoresist composition of Claim 22, wherein the fluoroolefin is tetrafluoroethylene.

24. (Previously Presented) The photoresist composition of Claim 19, wherein the fluorine-containing copolymer further comprises a unit containing a fluoroalcohol group or a protected fluoroalcohol group.

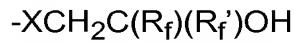
25. (Original) The photoresist composition of Claim 24, wherein the fluoroalcohol group or the protected fluoroalcohol group is derived from at least one ethylenically unsaturated compound containing a fluoroalcohol group having the structure:



wherein  $R_f$  and  $R_f'$  are the same or different fluoroalkyl groups of from 1 to 10 carbon atoms or taken together are  $(CF_2)_m$  wherein m is 2 to 10.

26. (Original) The photoresist composition of Claim 25, wherein  $R_f$  and  $R_f'$  are perfluoroalkyl groups.

27. (Previously Presented) The photoresist composition of Claim 19, wherein the fluorine-containing copolymer further comprises a fluoroalcohol group having the structure:

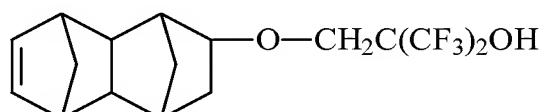
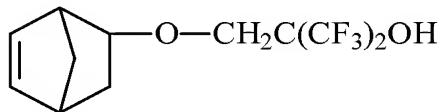
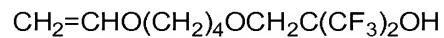
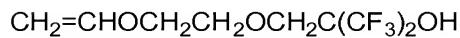
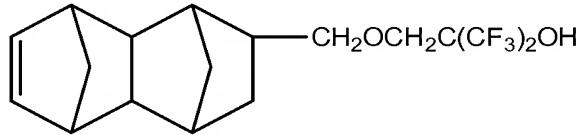
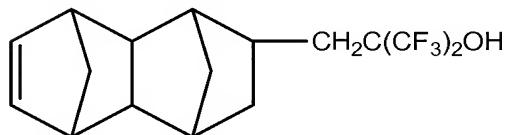
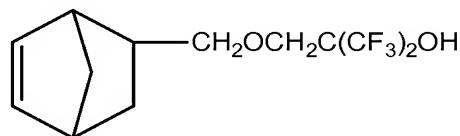
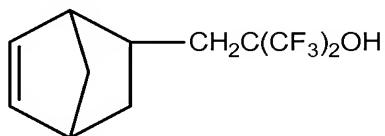


wherein  $R_f$  and  $R_f'$  are the same or different fluoroalkyl groups of from 1 to 10 carbon atoms or taken together are  $(CF_2)_m$  wherein m is 2 to 10; and X is an element from Group VA and VIA of the Periodic Table of the Elements.

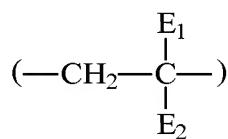
28. (Original) The photoresist composition of Claim 27, wherein X is selected from the group consisting of oxygen, sulfur, nitrogen and phosphorous.

29. (Original) The photoresist composition of Claim 28, wherein X is oxygen.

30. (Original) The photoresist composition of Claim 25, wherein the monomer containing the fluoroalcohol functional group or the protected fluoroalcohol group is selected from the group consisting of:



31. (Previously Presented) The photoresist composition of Claim 19, wherein the fluorine-containing copolymer further comprises at least one acid-containing or protected acid-containing group of structural unit:



wherein E<sub>1</sub> is H or C<sub>1</sub>-C<sub>12</sub> alkyl; E<sub>2</sub> is CO<sub>2</sub>E<sub>3</sub>, SO<sub>3</sub>E, or other acidic group; and E and E<sub>3</sub> are independently selected from the group of H, unsubstituted C<sub>1</sub>-C<sub>12</sub> alkyl, and heteroatom substituted C<sub>1</sub>-C<sub>12</sub> alkyl.

32. (Original) The photoresist composition of Claim 31, wherein the heteroatom is selected from the group consisting of oxygen, nitrogen, sulfur, halogen and phosphorus atoms.

33. (Original) The photoresist composition of Claim 32, wherein the heteroatom is oxygen, and the heteroatom substituted C<sub>1</sub>-C<sub>12</sub> alkyl further comprises a hydroxyl group.

34. (Original) The photoresist composition of Claim 31, wherein the acid-containing or protected acid-containing group is a carboxylic acid-containing monomer.

35. (Original) The photoresist composition of Claim 34, wherein the acid-containing or protected acid-containing group is selected from the group consisting of tert-butyl acrylate; 2-methyl-2-adamantyl acrylate; 2-methyl-2-norbornyl acrylate and acrylic acid.

36. (Previously Presented) The photoresist composition of Claim 19, wherein the fluorine-containing copolymer further comprises at least one group derived from a polar monomer.

37. (Original) The photoresist composition of Claim 19, wherein the photoactive component is a photoacid generator.

38. (Original) The photoresist composition of Claim 19, further comprising a dissolution inhibitor.

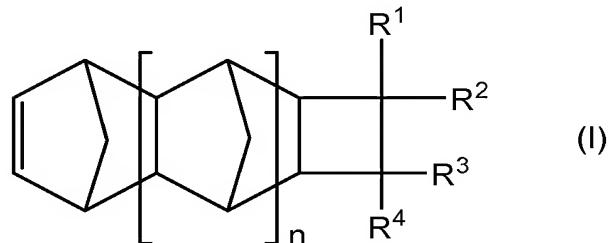
39. (Original) The photoresist composition of Claim 19, further comprising a solvent.

40. (Original) The photoresist composition of Claim 39, wherein the solvent is selected from the group consisting of an ether ester; a ketone; an ester; a glycol ether; a substituted hydrocarbon; an aromatic hydrocarbon; a fluorinated solvent and super critical CO<sub>2</sub>.

41. (Original) The photoresist composition of Claim 19, further comprising at least one additive selected from the group consisting of bases, surfactants, resolution enhancers, adhesion promoters, residue reducers, coating aids, plasticizers, and T<sub>g</sub> (glass transition temperature) modifiers.

42. (Previously Presented) A coated substrate comprising:

- (1) a substrate; and
- (2) a photoresist composition comprising:
  - (a) a fluorine-containing copolymer comprising a repeat unit derived from:
    - (i) at least one repeat unit derived from an ethylenically unsaturated compound having at least one fluorine atom covalently attached to an ethylenically unsaturated carbon atom; and
    - (ii) at least one repeat unit derived from an ethylenically unsaturated compound having the structure:



wherein n is 0, 1, or 2;

R<sup>1</sup>, R<sup>2</sup>, R<sup>3</sup> and R<sup>4</sup> are independently H, OR<sup>5</sup>, halogen, alkyl or alkoxy of 1 to 10 carbon atoms, optionally substituted by halogen or ether oxygens, Y, C(R<sub>f</sub>)(R'<sub>f</sub>)OR<sup>5</sup>, R<sup>6</sup>Y or OR<sup>6</sup>Y;

Y is COZ or SO<sub>2</sub>Z;

R<sup>5</sup> is hydrogen or an acid-labile protecting group;

R<sub>f</sub> and R<sub>f</sub>' are the same or different fluoroalkyl groups of 1 to 10 carbon atoms or taken together are (CF<sub>2</sub>)<sub>m</sub> where m is 2 to 10;

R<sup>6</sup> is an alkylene group of 1 to 20 carbon atoms, optionally substituted by halogen or ether oxygen;

Z is OH, halogen, or OR<sup>7</sup>; and

R<sup>7</sup> is an alkyl group of 1 to 20 carbon atoms, with the proviso that at least one of R<sup>1</sup>, R<sup>2</sup>, R<sup>3</sup> and R<sup>4</sup> is Y, OR<sup>5</sup>, C(R<sub>f</sub>)(R<sub>f</sub>')OR<sup>5</sup>, R<sup>6</sup>Y or OR<sup>6</sup>Y, and the proviso that if R<sup>1</sup> (or R<sup>3</sup>) is OH, R<sup>2</sup> (or R<sup>4</sup>) is not OH or halogen; and

(a) (b) a photoactive component.

43. (Original) The coated substrate of Claim 42, wherein the substrate is a microelectronic wafer.

44. (Original) The coated substrate of Claim 43, wherein the microelectronic wafer comprises a material selected from the group consisting of silicon, silicon oxide, silicon oxynitride, and silicon nitride.

45. (Currently Amended) A reaction product of quadricyclane quadraacyclane and a fluoroalkylbenzoate compound.